

AMENDMENTS TO THE CLAIMS

The following listing of claims will replace all prior versions and listings of claims in the application.

LISTING OF CLAIMS

1. – 4. (Cancelled).

5. (Currently Amended) A mask vapor deposition ~~device~~system comprising:
a deposition mask including silicon and being provided with an electrode, the mask having a wiring connected to the electrode to supply a charge to a mask pattern section, the deposition mask having an electrostatic chucking mechanism for attracting a subject for deposition using electrostatic attraction generated in the mask pattern section and controlling a and depositing of a deposition material on the deposition subject within a predetermined pattern, the mask being made of silicon and having positive and negative electrodes thereon;
an evaporation source for evaporating the deposition material; and
a unit for supplying the charge to the mask pattern section;
~~— a vacuum chamber,~~
wherein at least the deposition mask and the evaporation source are at least placed in the a vacuum chamber.

6. – 12. (Cancelled).

13. (Currently Amended) An apparatus for manufacturing a display panel so that an organic compound, which is used for forming electroluminescent elements, is deposited on a glass substrate with a predetermined pattern, the apparatus comprising:

~~an electrostatic chucking mechanism for attracting a glass substrate that is a subject for deposition using electrostatic attraction;~~

~~a deposition mask including silicon and being provided with an electrode, the mask having a wiring connected to the electrode to supply a charge to a mask pattern section, to be brought into close contact with a face of the glass substrate in order to deposit an organic material, which is used for forming electroluminescent elements on the glass substrate in a predetermined pattern, the face being reverse to that of the glass substrate attracted by the~~ the deposition mask having an electrostatic chucking mechanism for attracting a subject for deposition using electrostatic attraction generated in the mask pattern section and controlling a depositing of a deposition material on the deposition subject with a predetermined pattern, the mask being made of silicon;

~~an evaporation source for evaporating the organic material~~compound; and

~~a unit for supplying the charge to the mask pattern section;~~

~~a vacuum chamber,~~

~~wherein at least the mask mechanism, mask, and the source are at least placed in a~~ the vacuum chamber.

14. – 15. (Cancelled).